

Listing of the Claims:

Claims 1 - 10 (cancelled).

11. (Previously Presented) Local clean equipment comprising a chemical filter installed therein for trapping at least one of organic substances and inorganic substances and an air filter according to claim 27 installed therein for trapping suspended particulate substances in the air, said air filter being installed downstream of said chemical filter.

Claims 12 - 13 (cancelled)

14. (Previously Presented) Local clean equipment as defined in claim 31 which comprises a clean bench, a clean booth, a wafer stocker, wafer transfer space, and semiconductor fabrication equipment.

Claims 15 - 20 (cancelled)

21. (Previously Presented) A method for manufacturing a filter medium for an air filter to be used in the manufacture environment of a semiconductor device, comprising the steps of forming a non-woven fabric by binding fibers by a binder,

said binder having its chief ingredient of a polymer dispersion having a copolymer of a hydrophilic monomer and a hydrophobic monomer dispersed in water, and

obtaining said polymer dispersion by a polymerization step of dissolving the hydrophilic monomer in water, adding the hydrophilic monomer to this water solution and dispersing said hydrophobic monomer in said water solution, and adding a polymerization initiator to form said copolymer,

wherein in said polymerization step, a hydrophilic organic peroxide of cumen hydroperoxide, 2, 5-dimethylhexan-2, 5-hydroperoxide, or succinic acid peroxide is used as a polymerization initiator.

Claims 22 - 23 (cancelled)

24. (Previously Presented) A filter medium manufactured by the method of claim 21.

Claims 25 - 26 (cancelled)

27. (Previously Presented) An air filter comprising:
a filter medium for an air filter according to claim 24; and
a frame and a sealing material incapable of generating gaseous organic substances, wherein said air filter is assembled in a space free of gaseous organic substances.

Claim 28 (cancelled)

29. (Previously Presented) A clean room having an air filter according to claim 27 installed therein.

Claim 30 (cancelled)

31. (Previously Presented) Local clean equipment having an air filter according to claim 27 installed therein.

Claims 32 - 34 (cancelled)

35. (Currently Amended) A method for manufacturing ~~semiconductors~~ semiconductor devices wherein a silicon wafer for said ~~semiconductor~~ semiconductor device is processed in at least one of a clean room and local clean equipment having an air filter as defined in claim 27.

Claims 36 - 38 (cancelled).